

IN THE ABSTRACT:

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B<sup>2</sup> An exposure apparatus to be used with an excimer laser as a light source includes an optical system disposed along a path of excimer laser light, a chamber for accommodating the optical system therein and having an inside space being able to be replaced by a predetermined gas, a gas circulation mechanism having a gas circulation path for connecting a gas discharging port for discharging a gas from the chamber and a gas supplying port for supplying a gas into the chamber, and a switching device for selectively using plural purifiers disposed in the gas circulation path.

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